



Welcome United States Patent and Trademark Office

☐ Search Results[BROWSE](#)[SEARCH](#)[IEEE XPLORE GUIDE](#)

Results for "(((etch <or> strip) <and> hydrogen <and> plasma)<in>metadata)"

Your search matched 90 of 1144315 documents.

A maximum of 100 results are displayed, 25 to a page, sorted by Relevance in Descending order.

☒ e-mail[» View Session History](#)[» New Search](#)[» Key](#)

IEEE JNL IEEE Journal or Magazine

IEE JNL IEE Journal or Magazine

IEEE CNF IEEE Conference Proceeding

IEE CNF IEE Conference Proceeding

IEEE STD IEEE Standard

Modify Search

>>

☐ Check to search only within this results setDisplay Format: ☒ Citation ☐ Citation & Abstract

Select

Article Information

View: 1-25 |

1. Selective and deep etching of SiO₂ in high density low pressure fluorocarbon plasmas

Gaboriau, F.; Cartry, G.; Peignon, M.-C.; Cardinaud, Ch.;
 Plasma Science, 2002. ICOPS 2002. IEEE Conference Record - Abstracts. The 29th IEEE International Conf
 26-30 May 2002 Page(s):262

[AbstractPlus](#) | Full Text: [PDF\(200 KB\)](#) IEEE CNF


2. Wafer to wafer direct bonding using surfaces activated by hydrogen plasma treatment

Choi, W.B.; Ju, C.M.; Ju, B.K.; Sung, M.Y.;
 Electronics Manufacturing Technology Symposium, 1999. Twenty-Fourth IEEE/CPMT
 18-19 Oct. 1999 Page(s):148

[AbstractPlus](#) | Full Text: [PDF\(772 KB\)](#) IEEE CNF
3. Modeling of N₂/H₂ capacitively coupled plasma for low-k material etching

Chae-Hwa Shon; Makabe, T.;
 Plasma Science, IEEE Transactions on
 Volume 32, Issue 2, April 2004 Page(s):390 - 398

[AbstractPlus](#) | [References](#) | Full Text: [PDF\(496 KB\)](#) IEEE JNL


4. Time resolved Langmuir probe measurements in inductively coupled plasmas

Cartry, G.; Eon, D.; Raballand, V.; Gaboriau, F.; Peignon, M.C.; Cardinaud, Ch.;
 Plasma Science, 2002. ICOPS 2002. IEEE Conference Record - Abstracts. The 29th IEEE International Conf
 26-30 May 2002 Page(s):218

[AbstractPlus](#) | Full Text: [PDF\(196 KB\)](#) IEEE CNF
5. Enhanced oxygen plasma stripping of P⁺-implanted negative resist by hydrogen plasma pretreatment

Loong, W.-A.; Yen, M.-S.;
 Electronics Letters
 Volume 27, Issue 12, 6 June 1991 Page(s):1079 - 1081

[AbstractPlus](#) | Full Text: [PDF\(240 KB\)](#) IEE JNL


6. Diamond film formation using RF plasma CVD assisted by water vapor enhanced hydrogen radical so

Hiramatsu, M.; Yamada, K.; Mizuno, E.; Nawata, M.; Ikeda, M.; Hori, M.; Goto, T.;
 Plasma Science, 1995. IEEE Conference Record - Abstracts., 1995 IEEE International Conference on
 5-8 June 1995 Page(s):162 - 163

[AbstractPlus](#) | Full Text: [PDF\(200 KB\)](#) IEEE CNF